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 APPLICANT
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U.S. PATENT DOCUMENTS

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FOREIGN PATENT DOCUMENTS

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EXAMINER'S INITIALS	CITE NO.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.
		Vincent ARNAL et al. "A Novel SiO ₂ -Air Low K for Copper Dual Damascene Interconnect", Conference Proceedings ULSI XVI (2001) Materials Research Society pp. 71-77.
		B. SHIEH et al., "Air-Gap Formation During IMD Deposition to Lower Interconnect Capacitance", IEEE Electron Device Letters, Vol. 19, No. 1, January 1998
		B. P. SHIEH et al., "Integration and Reliability Issues for Low Capacitance Air-Gap Interconnect Structures", 1998 IEEE
		Vincent Arnal et al., "Optimization of CVD Dielectric Process to Achieve Reliable Ultra Low-k Air Gaps", Microelectronic Engineering 60 (2002) pp. 143-148

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